Subpicosecond Raman studies of non-equilibrium electron transport in an $In_{0.4}Ga_{0.6}N$ epilayer grown on GaN

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Abstract:

Field-induced electron transport in an $In_xGa_{1-x}N$ ($x \equiv 0.4$) sample grown on GaN has been studied by subpicosecond Raman spectroscopy. Non-equilibrium electron distribution and electron drift velocity due to the presence of piezoelectric and spontaneous fields in the $In_xGa_{1-x}N$ layer have been directly measured. The experimental results are compared with ensemble Monte Carlo calculations and reasonable agreements are obtained.

1. Introduction

Gallium nitride (GaN), aluminum nitride (AlN), indium nitride (InN) and their alloys have long been considered as very promising materials for device applications. ^{1,2} Semiconductor alloys such as $In_xGa_{1-x}N$ have been successfully used in the fabrication of blue-green light emitting diodes (LEDs) and laser diodes (LDs).²⁻⁷ Recently, growth of high quality InN as well as $In_xGa_{1-x}N$ have been demonstrated.⁸⁻¹⁰ The next natural step is to manufacture high performance InN and $In_xGa_{1-x}N$ electronic devices. In order to improve the design of these devices, knowledge of their electron transport properties is indispensable.¹¹ In this paper, we report experimental results on subpicosecond Raman studies of electric field-induced electron transport in an $In_xGa_{1-x}N$ ($x \equiv 0.4$) epilayer grown on GaN.

2. Sample and Experimental Technique

The Si doped $In_rGa_{1-r}N$ epilayer of about 0.15 μ m thick used in this work was grown on top of a 1.5 μ m GaN epilayer by metal organic chemical vapor deposition (MOCVD). Prior to the GaN growth, a 25 nm thick GaN buffer layer was grown on cplane sapphire at 550 °C. Subsequent epilayer growth was carried out at 1050 °C for GaN and 710 ${}^{0}C$ for $In_{x}Ga_{1-x}N$. Trimethylgallium (TMGa) and trimethylindium (TMIn) were used as the precursors. Nitrogen and hydrogen were used as carrier gases for $In_xGa_{1-x}N$ and GaN, respectively. High purity ammonia was used as the active nitrogen source. To vary In content in $In_{x}Ga_{1-x}N$, the TMIn flow rate was varied while other growth parameters were fixed. The $In_xGa_{1-x}N$ epilayer was doped by Si at a flow rate of 0.25 sccm of 10-ppm silane to improve the materials quality as well as to enhance the emission efficiency. GaN and $In_rGa_{1-r}N$ growth rate were 3.6 μ m/hr and 0.3 μ m/hr, respectively. The typical room temperature electron concentration and mobility of $In_{a}Ga_{1}N$ alloy is $2x10^{17} cm^{-3}$ and $160 cm^{2}/V \sec$, respectively, as determined by Hall effect measurements.

The output of the second harmonic of a cw mode-locked YAIG laser is used to synchronously pump a dual-jet R6G dye laser. The dye laser, which has a pulse width of FWHM $\cong 0.6$ ps, photon energy of $\hbar \omega \cong 2.17 eV$, a repetition rate of 76 MHz, was used to both excite and probe the $In_x Ga_{1-x}N$ sample. In our transient experiments, since the same laser pulse is used to excite and probe non-equilibrium electron transport, the experimental results represent an average over the duration of the laser pulse. The singleparticle scattering (SPS) spectra were taken in the $Z(X,Y)\overline{Z}$ scattering configuration where X = (100), Y = (010), Z = (001) so that only the SPS spectra associated with spindensity fluctuations were detected.¹² The backward-scattered Raman signal is collected and analyzed by a standard Raman system consisting of a double spectrometer, a photomultiplier tube. All the data reported here were taken at T = 300K.

3. Experimental results and discussions

Fig. 1(a) shows a typical SPS spectrum for an $In_xGa_{1-x}N$ ($x \equiv 0.4$) sample taken at T = 300K and for an electron-hole pair density of $n \cong 1x10^{18} \, cm^{-3}$. The SPS spectrum sits on a smooth background coming from the luminescence of E_0 bandgap of $In_xGa_{1-x}N$. Similar to previous studies on other III-V semiconductors such as GaAs, this background luminescence has been found to fit very well by an exponential function.¹³⁻¹⁵ The SPS spectrum is obtained by subtracting Fig. 1(a) from this luminescence background. Following the procedure described in details in Ref. 14, this subtracted spectrum (Fig. 1(b)) can then be very easily transformed to electron distribution function. The electron distribution thus obtained is shown in Fig. 1(c). The intriguing feature worthwhile pointing out is that the electron distribution function has been found to shift



Fig. 1: (a) A typical SPS spectrum taken at T = 300K and a photoexcited electron-hole pair density of $n \cong 1x10^{18} \text{ cm}^{-3}$. The SPS spectrum is found to lie on top of a luminescence background (soild curve) that can be fit very well by an exponential curve; (b) The SPS spectrum after the subtraction of luminescence background; (c) The electron distribution function obtained from (b).

toward the wavevector transfer \vec{q} direction – an indication of the presence of an electric field \vec{E} parallel to $-\vec{q}$. The electron distribution has a cut-off velocity of around $1.5x10^8 \, cm/\sec$, indicative of the band structure effects and the onset of electron intervalley scattering processes in $In_xGa_{1-x}N$. The electron drift velocity deduced from the measured electron distribution (Fig. 1c) is found to be $V_d \cong (3.8 \pm 0.4)x10^7 \, cm/\sec$.

We have also carried out an ensemble Monte Carlo (EMC) simulation¹⁶ for the transport of the photo-excited carriers in $In_xGa_{1-x}N$. Here, we treat polar optical phonon, acoustic phonons, intervalley phonons, and dislocation scattering. For dislocation scattering,^{17,18} we assumed that a defect density of $10^8 / cm^2$ existed in the $In_xGa_{1-x}N$ layer; however, it is found that because of the presence of much more efficient inelastic scattering processes, this elastic defect scattering process can affect the low field mobility but is not important for the high field transient experiments carried out here. Disorder-induced scattering due to In concentration fluctuations in $In_xGa_{1-x}N$ is not included in the EMC simulation because it is an elastic scattering process that does not affect the high field transport.¹⁶ Our EMC calculations predict that the electron drift velocity under our experimental conditions is $V_d = 3.5x10^7 cm/sec$. This result is in reasonable agreement with the experimental value quoted above.

There have been experimental evidences¹⁹⁻²² that an extremely large (of the order of MV/cm) electric field exists in the layer of $In_xGa_{1-x}N$ in the $GaN/In_xGa_{1-x}N/GaN$ structures as a result of huge lattice mismatch between $In_xGa_{1-x}N$ and GaN. We believe that, similar to the previous studies, the source of high electric field in the $In_xGa_{1-x}N/GaN$ sample studied in this work arises from a combination of the Proc. of SPIE Vol. 5352

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polarization field and the piezoelectric field. Although the direction of the net electric field is indicated in the shift of measured electron distribution (in this case, the net field points from GaN to $In_xGa_{1-x}N$ layers), the agreement between the experiment and the simulation is not sufficiently good to make a quantitative estimate of this field. Nevertheless, we can estimate the polarization field to be about 2.8 MV/cm, whereas the piezoelectric field is estimated to be some 50 % smaller, although we do not have a good measure of the piezo-electric constants in this alloy.^{22,23} We have extrapolated from the InN and GaN values, and this is not expected to be particularly accurate.

4. Conclusion

we have studied field-induced electron transport in an $In_xGa_{1-x}N$ ($x \equiv 0.4$) sample grown on GaN by subpicosecond Raman spectroscopy. Non-equilibrium electron distribution and electron drift velocity due to the presence of piezoelectric and spontaneous fields in the $In_xGa_{1-x}N$ layer have been directly measured. The experimental results are compared with ensemble Monte Carlo calculations and reasonable agreements are obtained.

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